

Crossed Andreev reflection in layered graphene structures

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HUNQUTECH



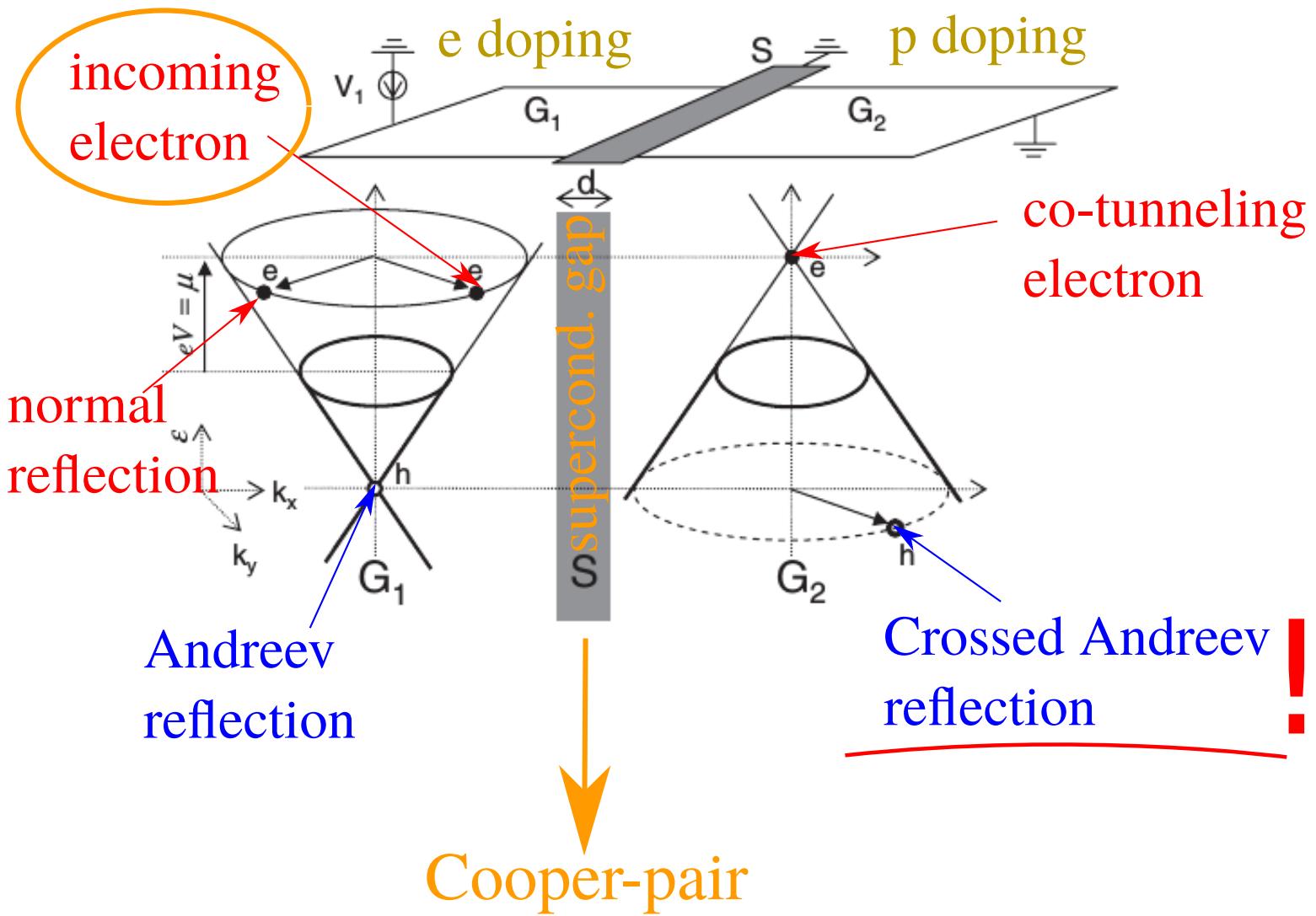
PROJECT
FINANCED FROM
THE NRDI FUND
MOMENTUM OF INNOVATION



Topograph meeting 2020.01.23.

Motivation

Proposal of J. Cayssol, PRL **100**, 147001 (2008):



"antisymmetric" gating:

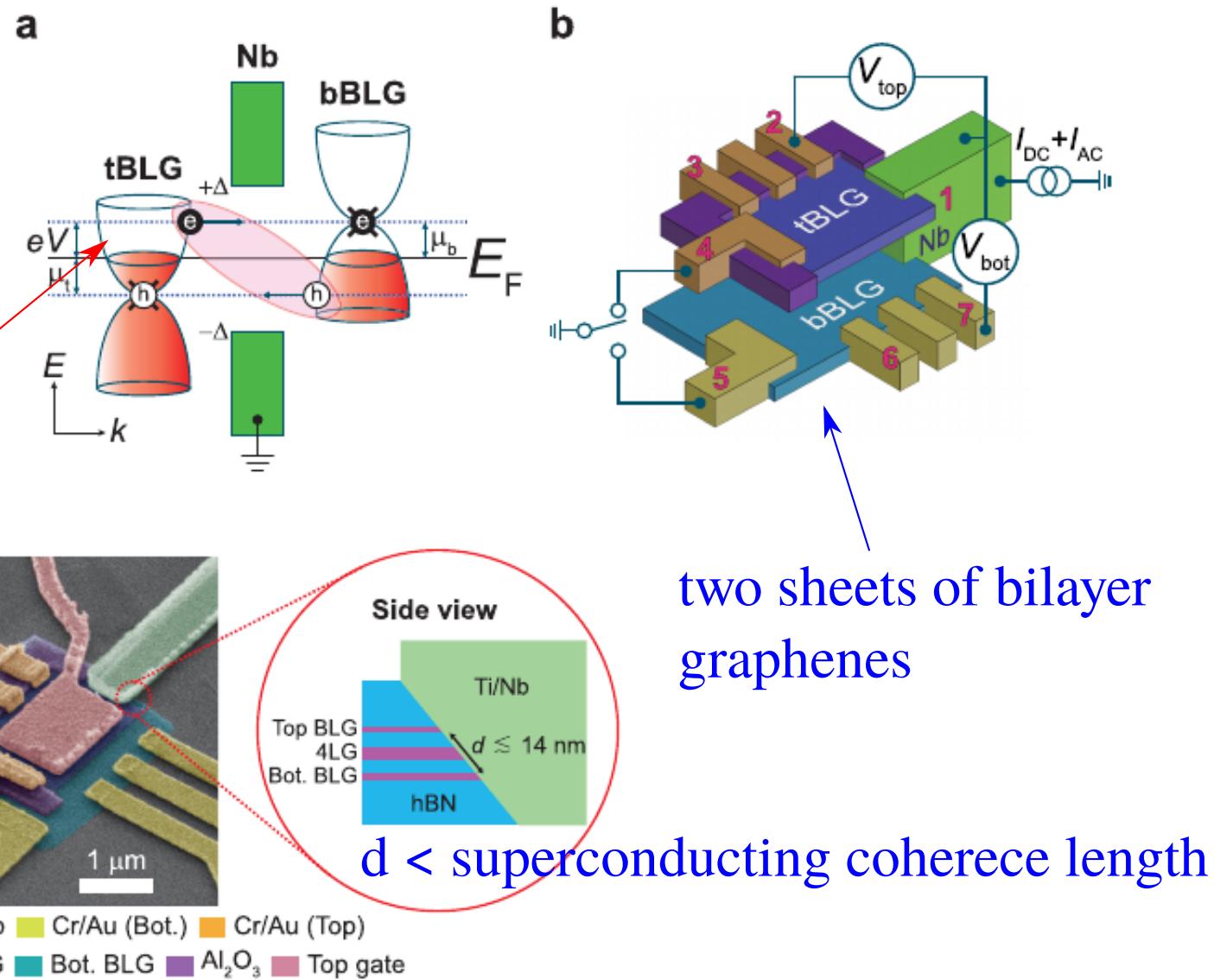
Andreev reflection and electron co-tunneling
are suppressed

Drawback:

- 1) the Dirac points should be within the sup. gap
- 2) at arbitrary energy the Andreev reflection and electron co-tunneling would not be suppressed

Experimental realization

Geon-Hyoung Park et. al., Nano Lett. 2019, 19, 9002–9007:

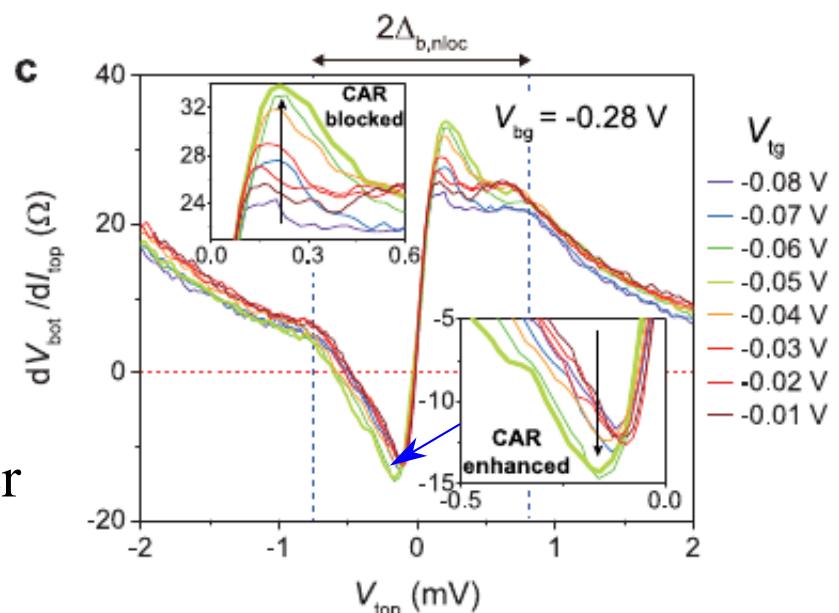


evidence for the crossed Andreev reflection (CAR) in the non-local differential resistance:

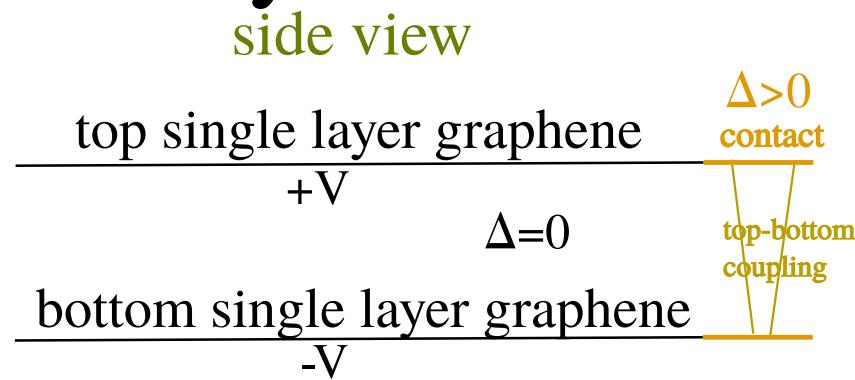
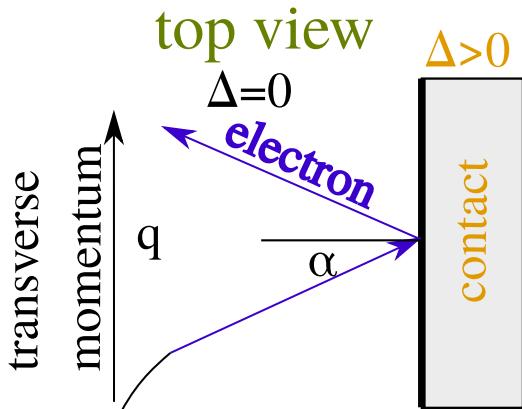
$$\frac{dV_{top}}{dI_{bot}}$$

top layer

bottom layer



Geometry

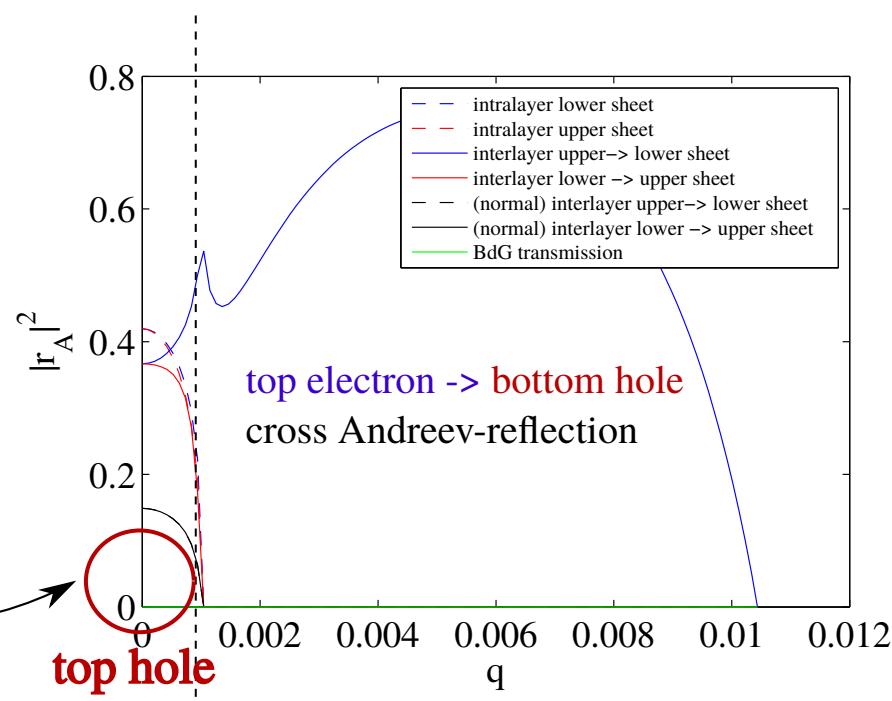
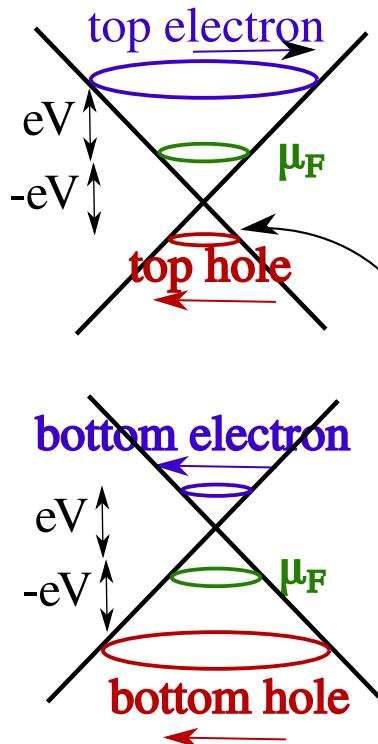


highly doped superconducting contact ($T < T_c$)

top-bottom coupling: single tight binding parameter for the "distance" between the layers

q can be translated into the incident angle α

Andreev Reflection Amplitude



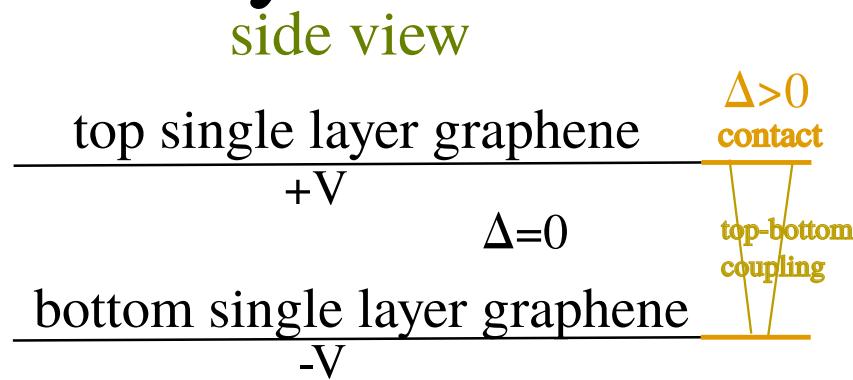
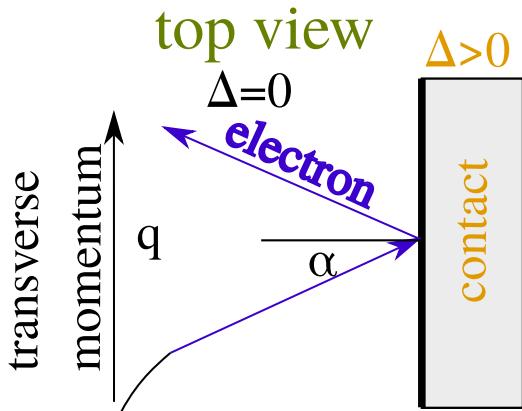
conditions:

$$V < \Delta ; |\mu - CNP| < \Delta$$

chemical potential

charge neutrality point

Geometry

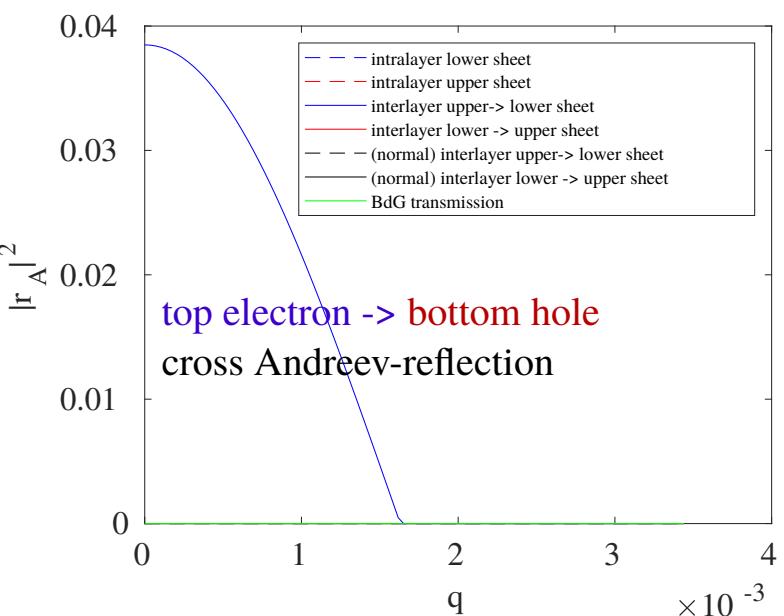
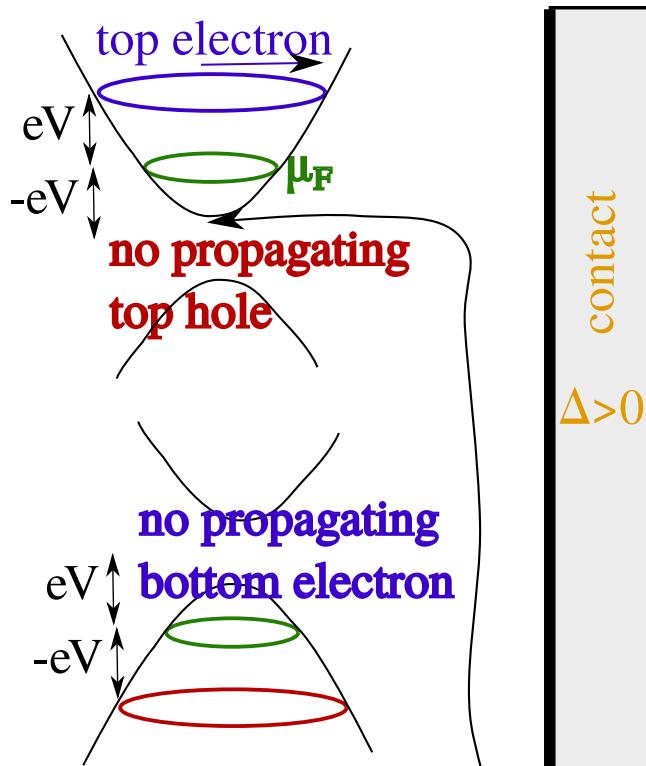


highly doped superconducting contact ($T < T_c$)

top-bottom coupling: single tight binding parameter for the "distance" between the layers

q can be translated into the incident angle α

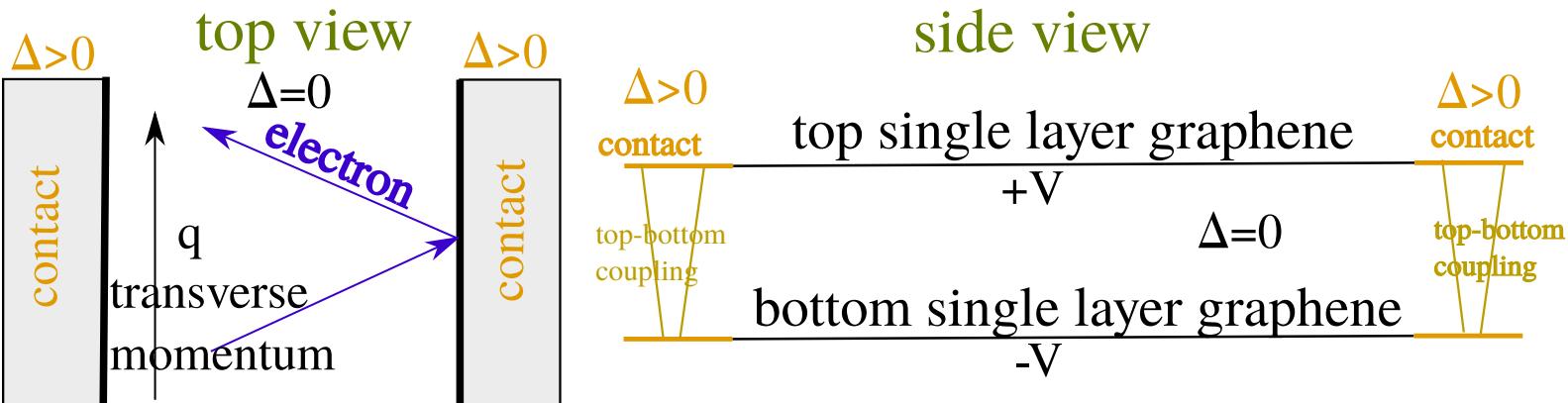
Andreev Reflection Amplitude



conditions:
 $V < \Delta$; $|\mu\text{-band edge}| < \Delta$

chemical potential

Geometry

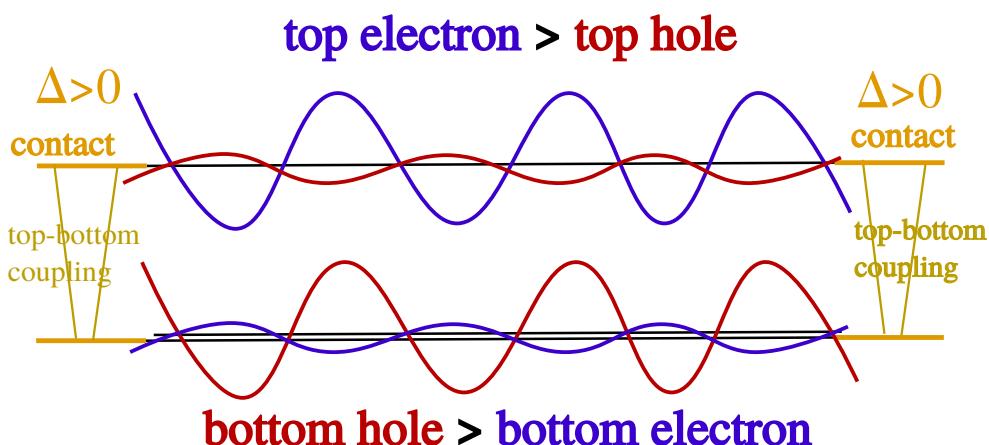


highly doped superconducting contacts ($T < T_c$)

top-bottom coupling: single tight binding parameter for the "distance" between the layers

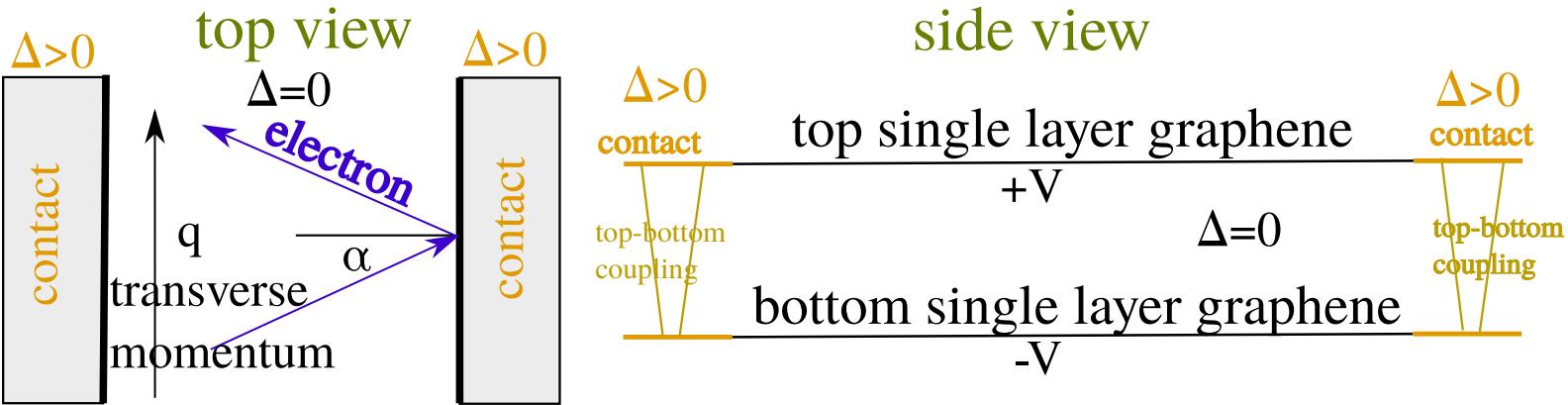
Expectation

side view



resonantly enhanced spilling of the electron and hole wave function?

Geometry

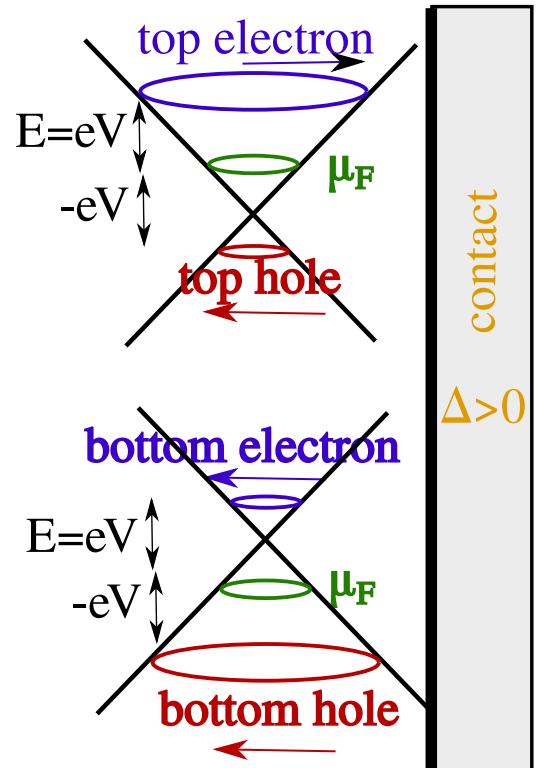


highly doped superconducting contacts ($T < T_c$)

top-bottom coupling: single tight binding parameter for the "distance" between the layers

Density of States

at the center of the central region
on the upper sheet

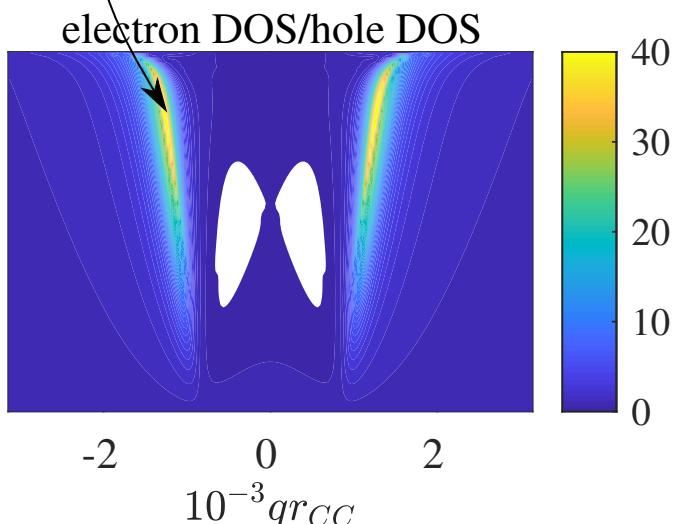
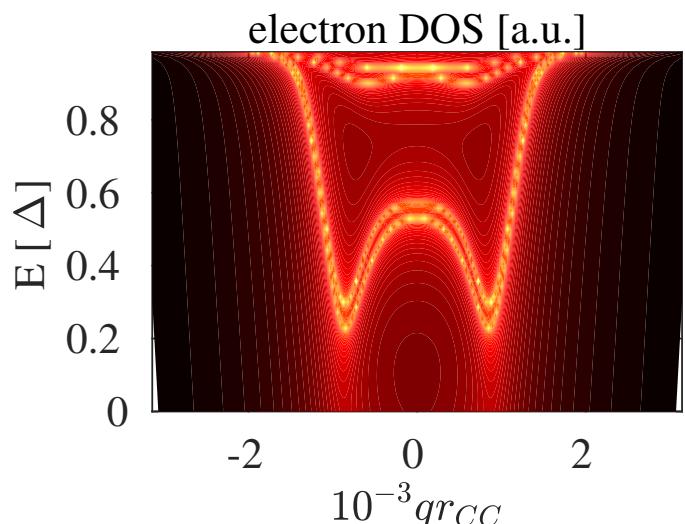


$$\text{DOS}_{\text{electron}} > \text{DOS}_{\text{hole}}$$

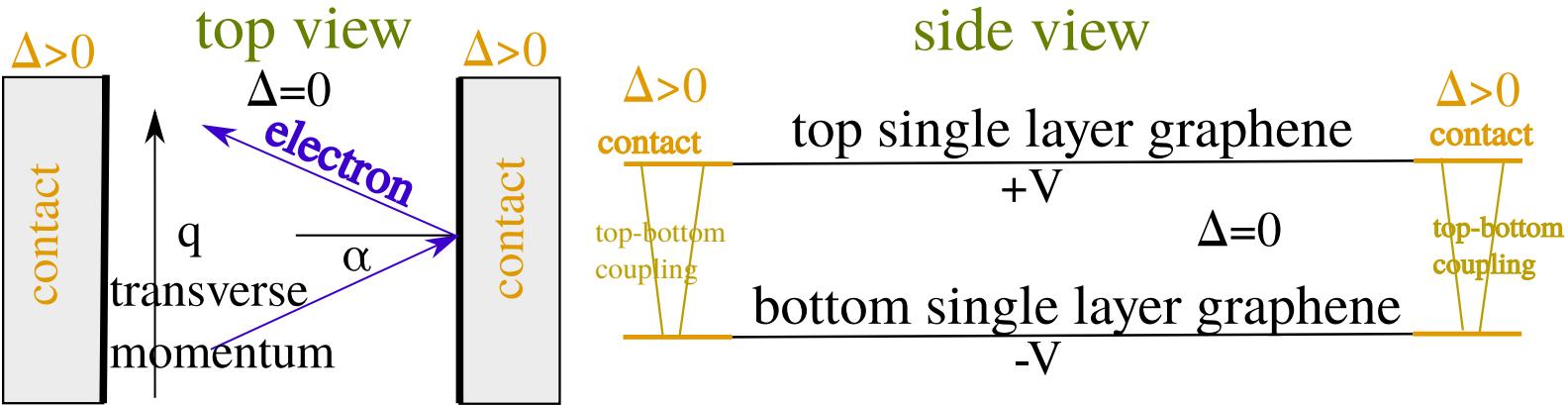
only at higher incident angles α
where there is no propagating hole state

$$\Delta\varphi = \pi/3 \text{ (phase difference)}$$

junction length = 500 nm



Geometry



highly doped superconducting contacts ($T < T_c$)

top-bottom coupling: single tight binding parameter for the "distance" between the layers

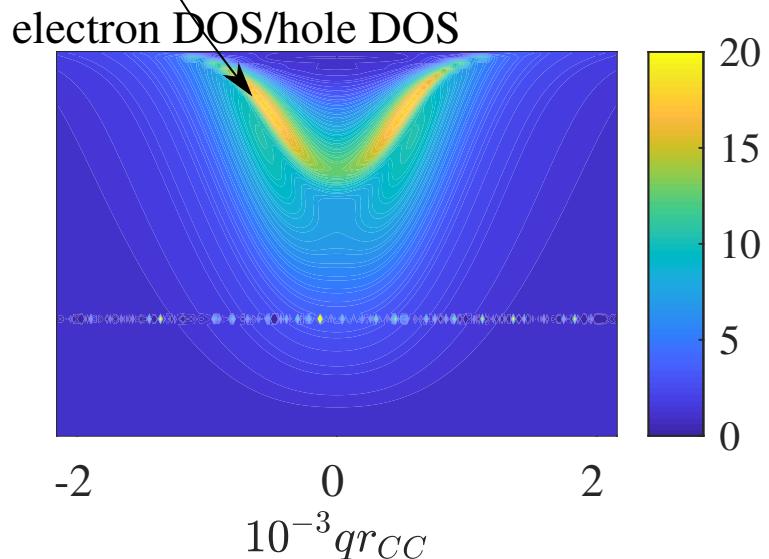
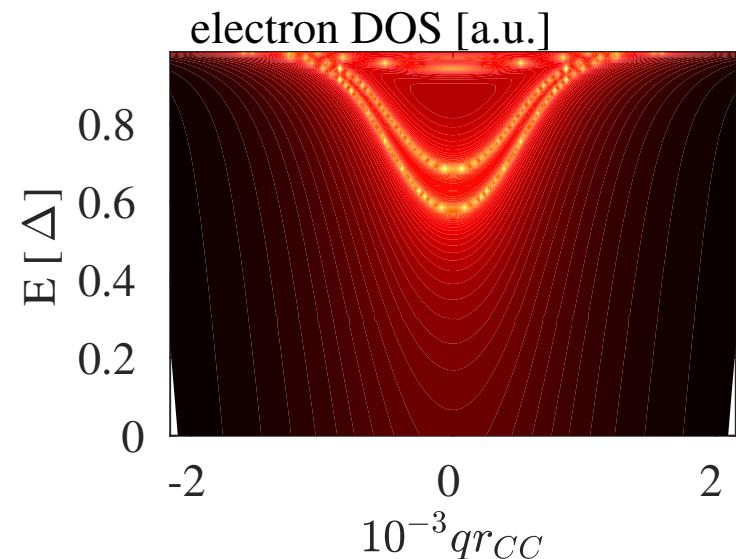
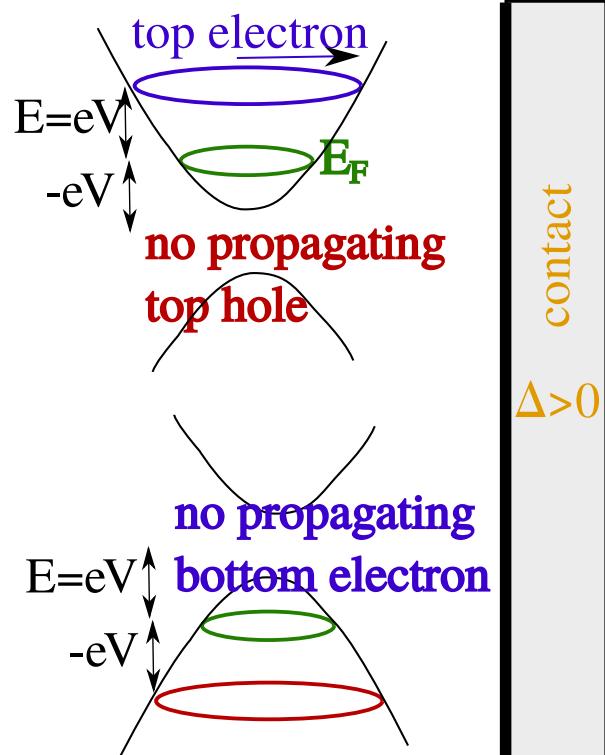
Density of States

at the center of the central region
on the upper sheet

$$\text{DOS}_{\text{electron}} > \text{DOS}_{\text{hole}}$$

for almost all incident angles except for
 $(\alpha =) q = 0$.

$\Delta\varphi = \pi/3$ (phase difference)
junction length = 500 nm



Density of States

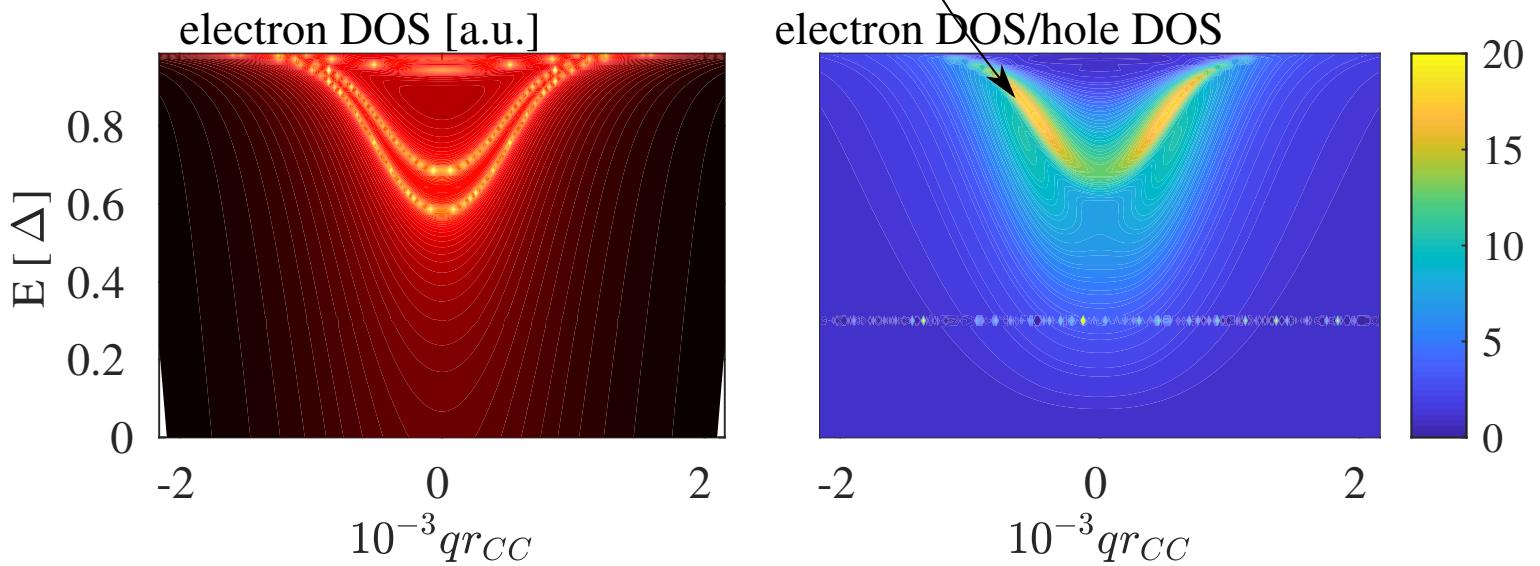
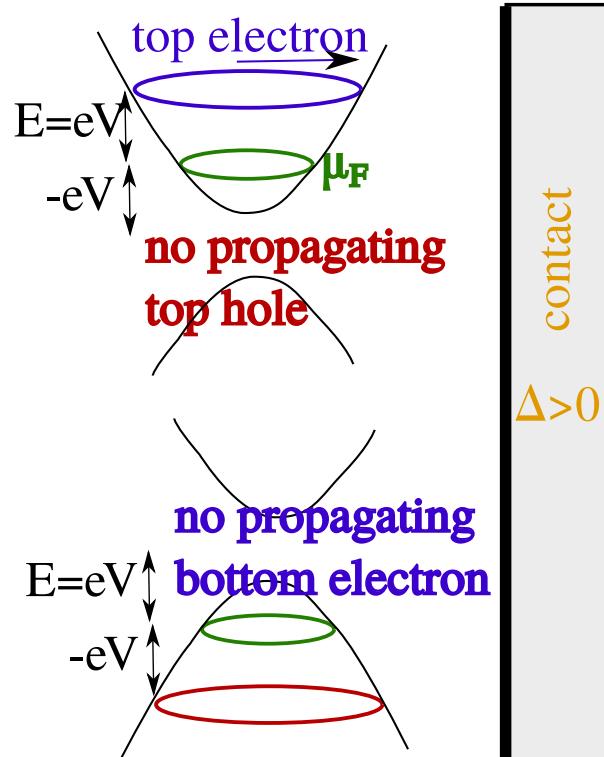
at the center of the central region
on the upper sheet

$$\text{DOS}_{\text{electron}} > \text{DOS}_{\text{hole}}$$

for almost all incident angles except for
 $(\alpha=) q=0$.

$$\Delta\varphi = \pi/3 \text{ (phase difference)}$$

$$\text{junction length} = 500 \text{ nm}$$



The decaying length of the hole states for gap $|eV\text{-band edge}| = 1 \text{ meV}$
at incident angle $\alpha=0$

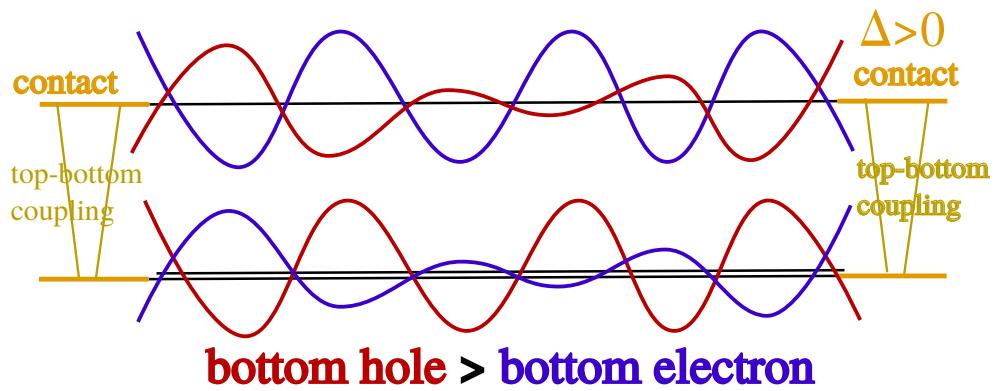
$$L \sim 1/\text{imag}(k_0)$$

$$\hbar v_F k_0 \sim |eV\text{-band edge}|$$

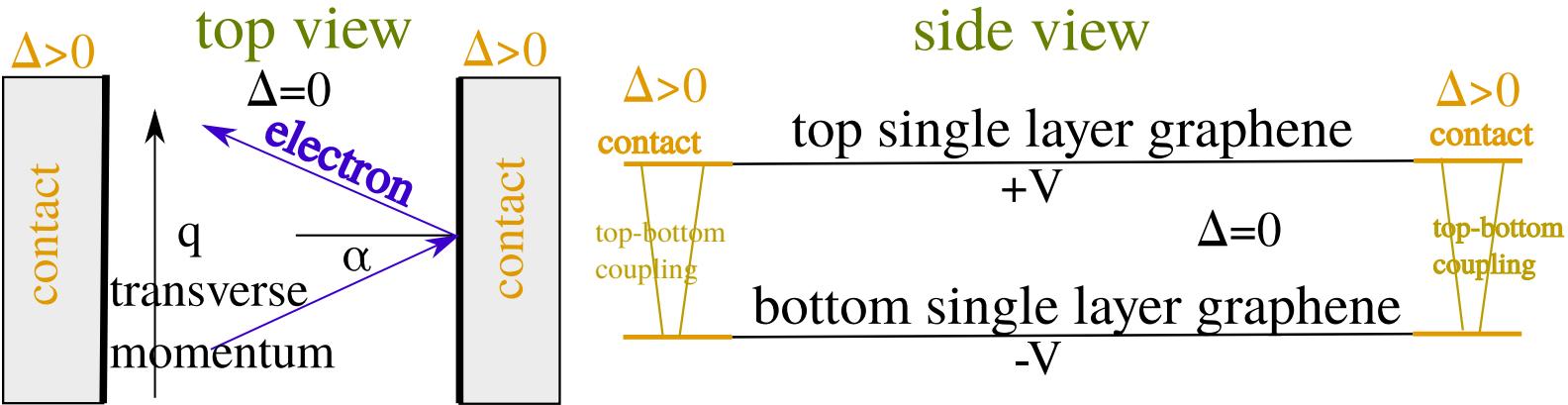
$$L \sim 600 \text{ nm}$$

$$\Delta > 0$$

top electron > top hole



Geometry



highly doped superconducting contacts ($T < T_c$)

top-bottom coupling: single tight binding parameter for the "distance" between the layers

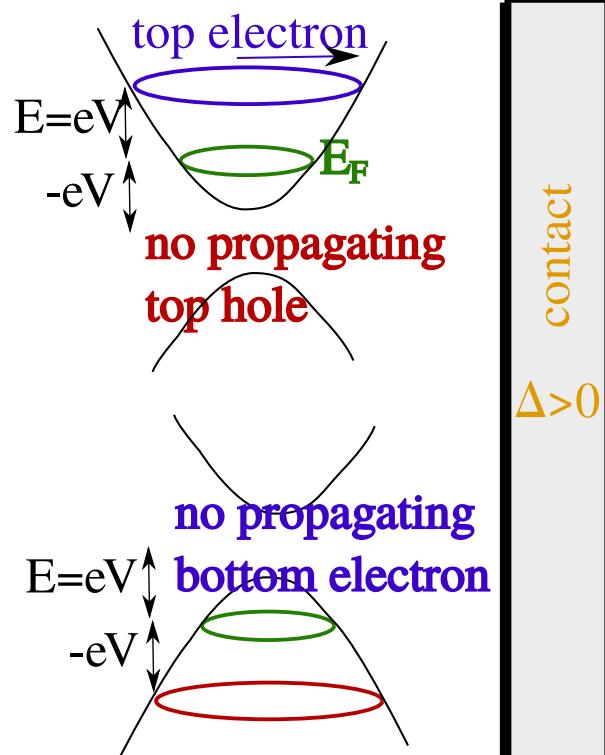
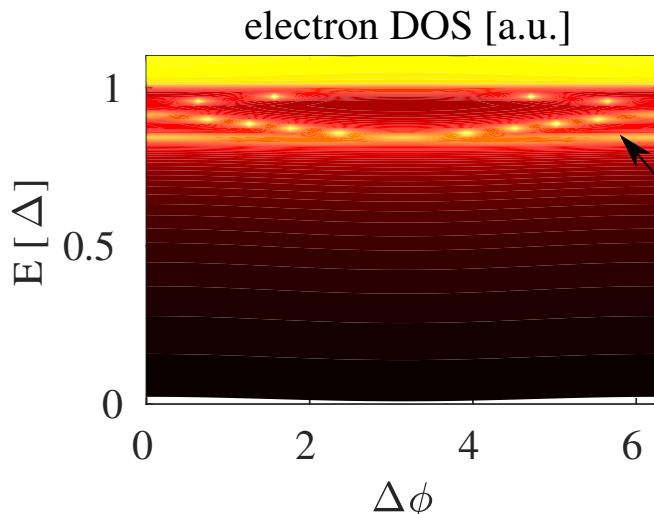
Density of States

at the center of the central region
on the upper sheet

$$\text{DOS}_{\text{electron}} > \text{DOS}_{\text{hole}}$$

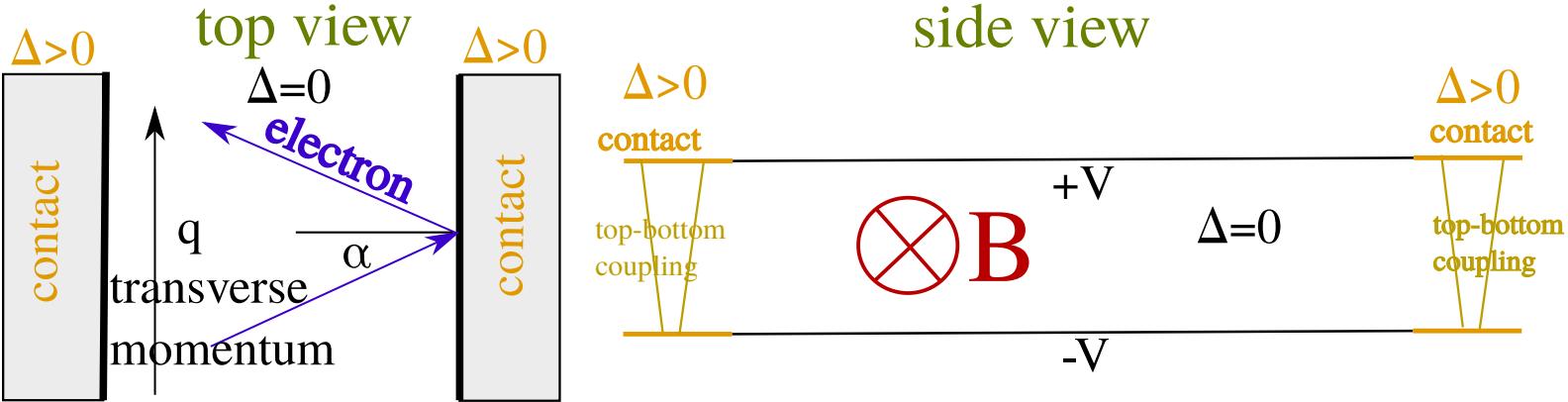
at $\Delta\phi$ close to π

calculated for specific $q > 0$ ($\alpha > 0$)
junction length = 500 nm



non-dispersive state is localized to one of the S-G interfaces

Geometry



Density of States

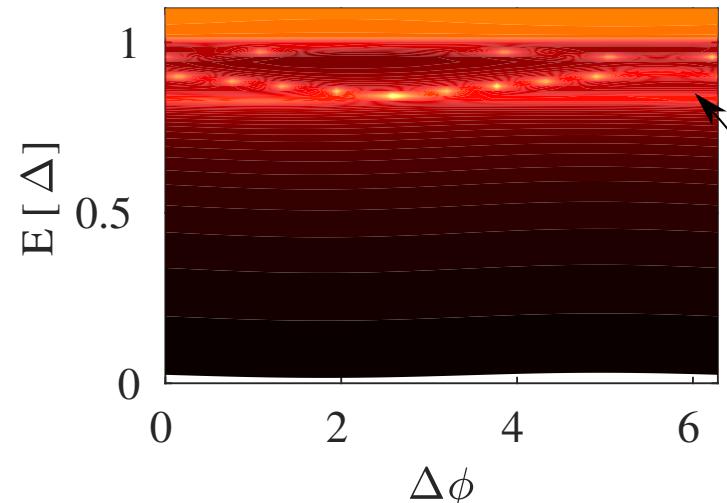
at the center of the central region
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$$\text{DOS}_{\text{electron}} > \text{DOS}_{\text{hole}}$$

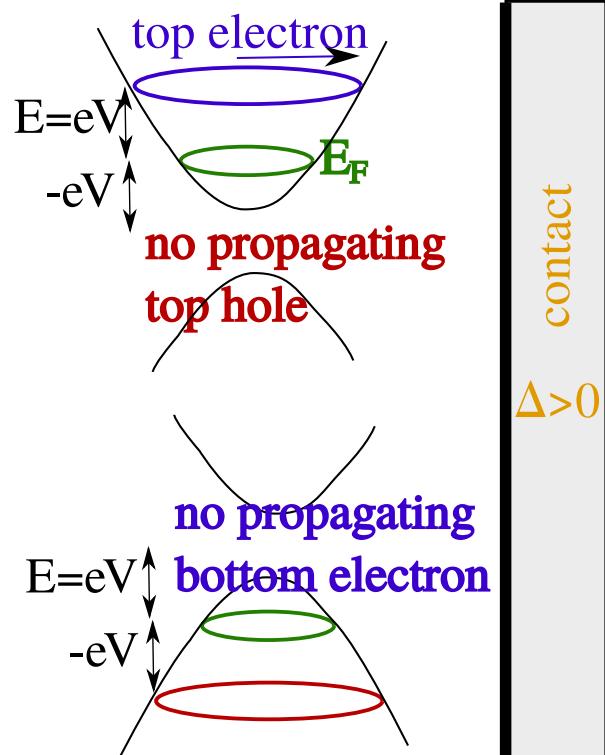
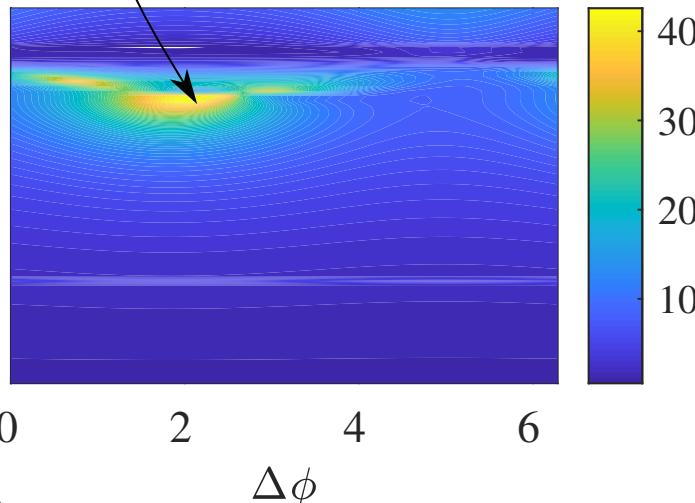
the maximum is shifted due to the
magnetic flux

calculated for specific $q > 0$ ($\alpha > 0$)
and for a specific magnetic flux

electron DOS [a.u.]



electron DOS/hole DOS



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- ➡ NKFIH within the Quantum Technology National Excellence Program (Project No. 2017-1.2.1-NKP-2017-00001),
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- ➡ OTKA PD123927, K123894 and K108676